

**Notice of References Cited**

Application/Control No.

09/938,435

Applicant(s)/Patent Under  
Reexamination  
WON ET AL.

Examiner

Christopher G. Paulraj

Art Unit

1773

Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,427,623	08-2002	Ko	118/723 E
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	M	US-			

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Ekbundit et al., Characterization of film uniformity in LPCVD TEOS Vertical Furnace, 2002 IEEE/SEMI Advanced Semiconductor Manufacturing Conference, pp 38-42
	V	Lee et al., The Effect of Patterned Susceptor on the Thickness Uniformity of Rapid Thermal Oxides, IEEE Transactions on Semiconductor Manufacturing, vol. 12, no. 3, pp 340-344
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.